

Photomask Equipment – Business Update

Yuta Nagai, Vice President Photomask Equipment – Capital Markets Day 2023



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Markets and set-up to enable profitable growth

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New markets for our technology

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Summary and outlook



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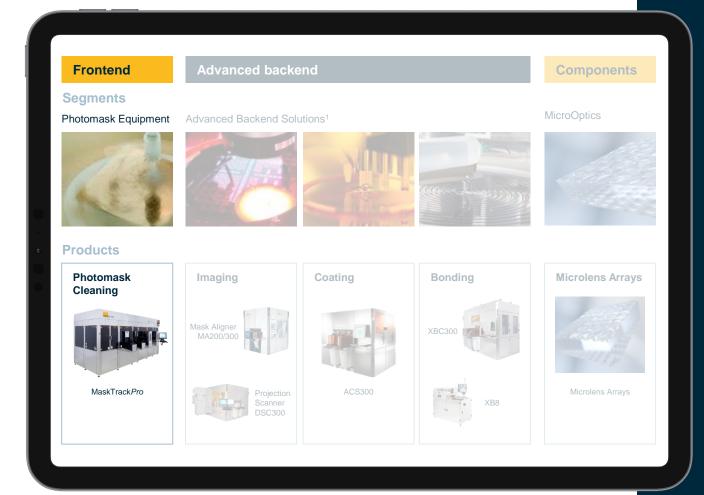
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Photomask Equipment at a glance





Our business in numbers

219 FTEs

Our employees, mainly in production, R&D, marketing and sales

~49 in € million

FY2022 revenue, represents 16% of the Group's sales

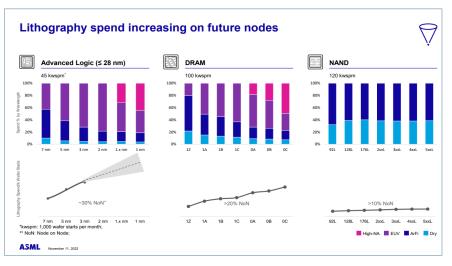
~131 in € million

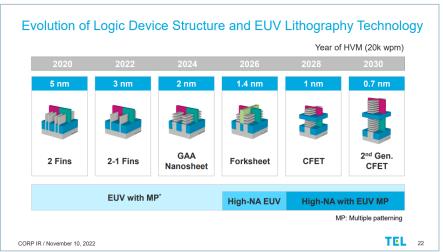
FY2022 order entry, represents 30% of the Group's order entry

No.1

Clear market leader in both, Cleaning and Bake & Develop

Market follows Moore's Law with EUV-L





Source: ASML, Investor Day 2022 | TEL, Q2 FY2023 Financial Announcement presentation

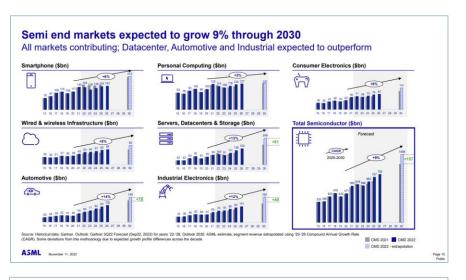


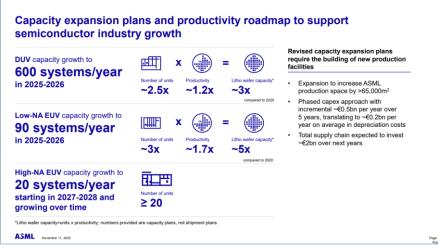
Capability demand will be mainly driven by Extreme Ultraviolet Lithography (EUV-L) toward device structures planned beyond 5 nm node.

Conventional litho will continue to be used mainly for flash memory (NAND), while the use in logic and volatile memory (DRAM) are decreasing.

Well-filled investment pipeline in new frontend fabs across the world drives growth in Photomask Equipment as additional lithography capacities require photomasks.

Semi end market growth is 9% CAGR





Source: ASML, Investor Day 2022



The semi end market annual growth rate of around 9%, doubling the revenue from 2020 to 2030.

Faster node migration and stronger outlook on growing servers and emerging markets.

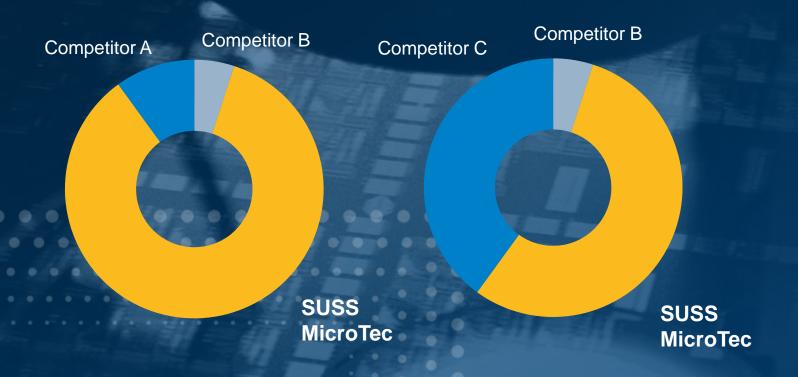
Mature market is mainly driven by smart grids and automotive.

Based on ASML's expansion plan, the average demand for high-end photomask cleaning will be 10-20 systems per year.

SUSS MicroTec is a market leader today

Cleaning system

Bake & Developer (BD) system



Achievements

2022

Order Entry

Revenue

~ €131m

~ €49m

- Our latest platform, MaskTrack X, is qualified and used for first EUV-L 5nm production at the largest foundry in the world (2020)
- Received supplier award from a leading maskshop, AMTC (2021)
- Highest order volume in our history (2022)
- Growing number of installations in China (2022)



MaskTrack X Cleaner



Supplier award from AMTC

SUSS MicroTec calculation based on installation base 2010-2023

We have an existing set-up for next innovation in place

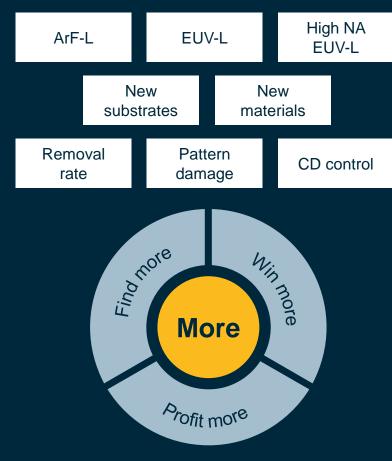


Technology scouting Our expertise Roadmap alignment

- Customer-specific requirements
- Continuous improvement
- Consortia and conferences
- Partnership with industrial leaders

- **Tool control**
 - Machine learning
 - Media knowledge
 - Surface preparation
- 2 **Cleaning systems**
 - Acid-less organic removal
 - Physical force removal
 - **EUV** frontside protection
- **Bake & Developer systems**
 - Process optimization
 - Dynamic curtain control
 - 25 zone hotplate

Field qualification (selection)



ArF-L is ArF Immersion Lithography

Maintaining and expanding business by R&D

SÜSS MicroTec

Technology roadmap and technology orientation is completed along a leading customer's roadmap.

New technologies enabling to go **EUV-3nm** and below is under final field test.

Successful launch of MaskTrack Smart Bake and Developer in 2022.

Development of new platform, MaskTrack Smart Cleaner, has started for official launch in 2024.

Enhanced AI capability is under development with technology partner.

MaskTrack Smart

Bake and Developer



Within-Tool-Analysis

Economic growth along with the market

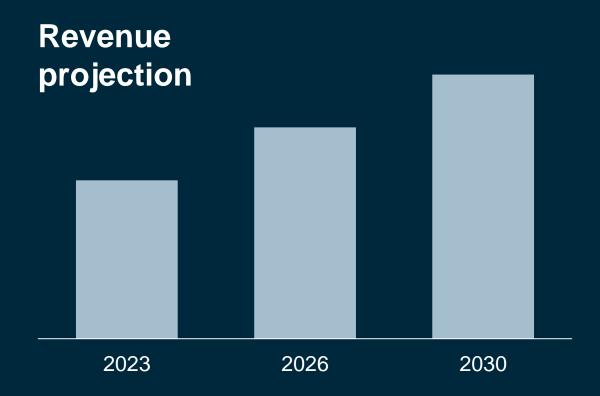




Leading competitive position drives the growth with the market dynamics in frontend lithography

The release of a new valueadded product, **MaskTrack Smart**, will allow us to keep our dominant market position

More than €700 million cumulated revenue SUSS MicroTec Photomask Equipment target 2023-2030





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Leverage existing assets to pursue wafer cleaning market





Green in photomask cleaning

Existing high-end cleaning knowledge and the process know-how to remove fine particles without the use of acid and solvent chemicals.



Expertise in manufacturing wafer systems

Existing experience and procedure to design and manufacture backend wafer systems, driven by new group R&D.

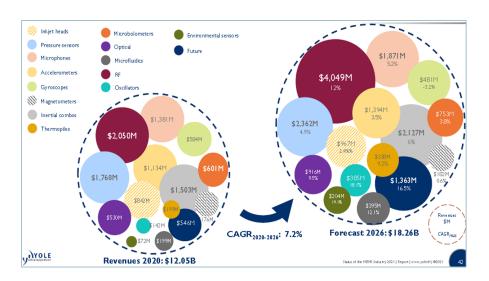


Market presence and global infrastructure

Existing market relationships and service infrastructure in Advanced Backend Solutions business unit, such as MEMS and Advanced Packaging.



MEMS cleaning is our first target market



MEMS cleaning

total addressable market (TAM) in \$ million



Source: Yole, Status of the MEMS Industry 2021 | SUSS MicroTec calculation based on market information





Economic motivation

- Total addressable market (TAM) for MEMS cleaning equipment in 2022 is US\$ 180M
- Predicted to grow at an annual rate of 10% to US\$ 350M in 2030



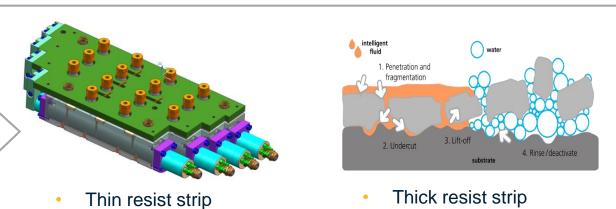
Market requirement

- MEMS cover large and ever-growing applications space, requiring highly customized equipment
- Numerous polymers used in production require unique strip and cleaning technologies
- Conventional chemistry (NMP) used as main strip media increasingly restricted by government regulations
- Industry search for alternative solutions is in full swing
- Penetrate later into Advanced Packaging and Power Device in wafer cleaning

New green solutions to replace hazardous chemicals in MEMS cleaning









Photomask cleaning solutions

- Insite-UV technology for fast strip of organic materials without using Acid or solvent chemical
- IP protected



CrustBuster technology

Single wafer processing

Final Cleaning

- Wafer coverage up to 300 mm
- IP protected

New

TurblenStrip technology

Polyimide removal

- Batch processing
- Magic green media
- IP protected, owned by partner

New

SUSS GREEN solutions

- Favorite Cost-of-Ownership
- Eliminate conventional Acid and solvent chemicals

Our solutions enable our customers to save annual running cost and increase efficiency



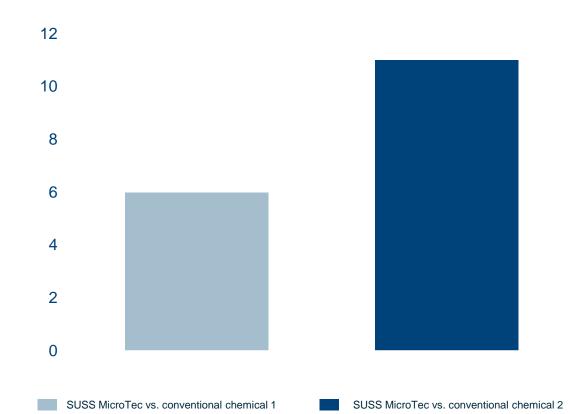


Total saving to remove 10 um resist shows a clear **Cost-of-Ownership benefit** on SUSS MicroTec **Green** Solutions.

Other than the conventional technology, our technology is complete within the SUSS MicroTec tool and does not require additional costs or processes for pre-or post-treatment.

Best-in-class Cost-of-Ownership

[relative savings in € million per year and tool]



Wafer clean is the largest growth factor



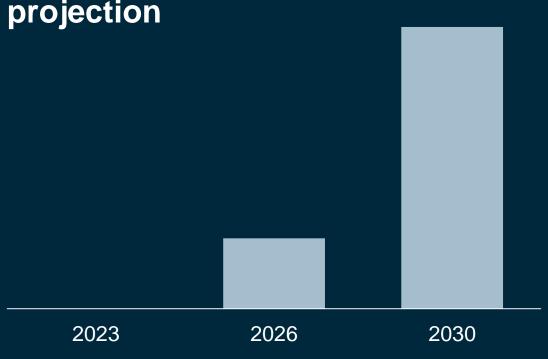


SUSS will target MEMS application first and transfer its know-how in cleaning to the advanced package and the power device of micron scale wafer applications.

We will bring a revolutionary **Green Solution** to the industry, aggressively capture market share, and become a major growth factor.

more than €500 million cumulated revenue SUSS MicroTec wafer cleaning target 2023-2030

Revenue projection





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Significant revenue growth

Photomask Equipment including wafer cleaning in 2023-2030



- The semi-end market CAGR of around 9% and a doubling of semiconductor revenue (2020-2030)
- Advanced wafers will follow the Moore's law with EUV-L and require further innovation
- Photomask equipment demand increases in proportion to lithography demand



- ASML plans to increase capacity and capability on EUV-L systems
- SUSS MicroTec aims to maintain the dominant market share for photomask manufacturing and maintenance
- Targeting Green solution with outstanding CoO model in primary MEMS industry
- Extend later for other backend application